

<b>Notice of References Cited</b>	Application/Control No. 09/818,073		Applicant(s)/Patent Under Reexamination WOJTCZAK ET AL.	
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#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6224785	05-2001	Wojtczak et al.	252
1	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

#### FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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	R					
	S					
	T					

#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Hidetoshi et al. Cleaner for Semiconductor Device and Production of Semiconductor Device, ((March 7, 1997), Electronic-English translation of JP 09-062013, pp. 1-4.
	V	Wojtczak et al., Improved Post Plasma Ashing Wafer Cleaning Formulation, (January 8, 1998), PCT, WO 98/00244.
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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